

(12) International Application Status Report

Received at International Bureau: 11 April 2018 (11.04.2018)

Information valid as of: 17 July 2018 (17.07.2018)

Report generated on: 22 February 2019 (22.02.2019)

(10) Publication number:

WO2018/181809

(43) Publication date:

04 October 2018 (04.10.2018)

(26) Publication language:

Japanese (JA)

(21) Application Number:

PCT/JP2018/013444

(22) Filing Date:

29 March 2018 (29.03.2018)

(25) Filing language:

Japanese (JA)

(31) Priority number(s):

2017-073294 (JP)

(31) Priority date(s):

31 March 2017 (31.03.2017)

(31) Priority status:

Priority document received (in compliance with PCT Rule 17.1)

2017-073295 (JP)

31 March 2017 (31.03.2017)

Priority document received (in compliance with PCT Rule 17.1)

(51) International Patent Classification:

H01L 21/306 (2006.01); *B08B 3/02* (2006.01); *H01L 21/208* (2006.01); *H01L 21/304* (2006.01)

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(54) Title (EN): PROCESSING DEVICE AND PROCESSING METHOD

(54) Title (FR): DISPOSITIF ET PROCÉDÉ DE TRAITEMENT

(54) Title (JA): 処理装置および処理方法

(57) Abstract:

(EN): Provided are a processing device (system) and a processing method with which good quality roll-to-roll processing can be performed simply and easily on both sides of a substrate under atmospheric pressure. A processing device (system) for processing a substrate using a mist or liquid droplets including a processing agent is provided with an accumulation unit for accumulating the mist or liquid droplets, and an impregnation unit for impregnating the substrate with the accumulated mist or liquid droplets. Using the processing device, the mist or liquid droplets are accumulated, and the substrate is processed by impregnating the substrate with the accumulated mist or liquid droplets.

(FR): L'invention concerne un dispositif (système) de traitement et un procédé de traitement qui permettent de réaliser un traitement de rouleau à rouleau de bonne qualité simplement et facilement des deux côtés d'un substrat sous pression atmosphérique. Un dispositif (système) de traitement destiné à traiter un substrat en utilisant un brouillard ou des gouttelettes de liquide comprenant un agent de traitement est pourvu d'une unité d'accumulation destinée à accumuler le brouillard ou les gouttelettes de liquide, et d'une unité d'imprégnation destinée à imprégner le substrat avec le brouillard ou les gouttelettes de liquide accumulés. En utilisant le dispositif de traitement, le brouillard ou les gouttelettes de liquide sont accumulés et le substrat est traité par imprégnation du substrat avec le brouillard ou les gouttelettes de liquide accumulés.

(JA): 大気圧下で、基板の両面において、簡便且つ容易に良質な処理をロール・トゥ・ロールで可能な処理装置(システム)および処理方法を提供する。処理剤を含むミストまたは液滴を用いて基体を処理する処理装置(システム)であって、前記ミストまたは液滴を滞留させる滞留部と、滞留させている前記ミストまたは液滴を前記基体に含浸させる含浸部とを備えている処理装置を用いて、前記ミストまたは液滴を滞留させ、滞留させている前記ミストまたは液滴を前記基体に含浸させて前記基体を処理する。

International search report:

Received at International Bureau: 16 July 2018 (16.07.2018) [JP]

International Report on Patentability (IPRP) Chapter II of the PCT:

Not available

(81) Designated States:

AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, JO, JP, KE, KG, KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW

European Patent Office (EPO) : AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR

African Intellectual Property Organization (OAPI) : BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG

African Regional Intellectual Property Organization (ARIPO) : BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW

Eurasian Patent Organization (EAPO) : AM, AZ, BY, KG, KZ, RU, TJ, TM